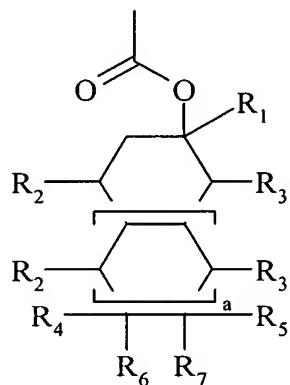


This listing of claims will replace all prior versions, and listings, of claims in the application:

**LISTING OF CLAIMS:**

1. (Currently Amended) A polymer containing a group of the following formula (1) and having a weight average molecular weight of 1,000 to 500,000,



(1)

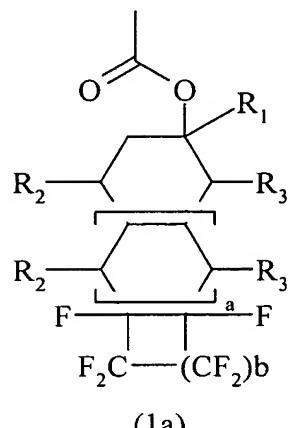
wherein R<sup>1</sup> is hydrogen, fluorine or a straight, branched or cyclic alkyl or fluorinated alkyl group of 1 to 20 carbon atoms, and R<sup>2</sup> and R<sup>3</sup> bond together to form a ring such that each is an alkylene group of 1 to 20 carbon atoms which optionally contains an oxygen, sulfur or nitrogen hetero atom,

R<sup>4</sup> and R<sup>5</sup> each are hydrogen or fluorine,

R<sup>6</sup> and R<sup>7</sup> each are hydrogen, fluorine or a straight, branched or cyclic alkyl or fluorinated alkyl group of 1 to 20 carbon atoms, in which case at least one of R<sup>6</sup> and R<sup>7</sup> is a fluorinated alkyl group of 1 to 20 carbon atoms contains at least one fluorine atom, or alternatively R<sup>6</sup> and R<sup>7</sup> bond together to form a ring and in that event, each is a straight, branched or cyclic alkylene or fluorinated alkylene group of 1 to 20 carbon atoms, and

“a” is 0 or 1.

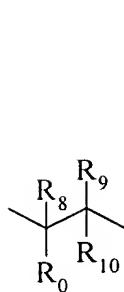
2. **(Previously presented)** A polymer containing a group of the following formula (1a) and having a weight average molecular weight of 1,000 to 500,000:



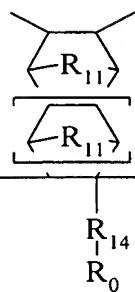
(1a)

wherein R<sup>1</sup> to R<sup>3</sup> each are hydrogen, fluorine or a straight, branched or cyclic alkyl or fluorinated alkyl group of 1 to 20 carbon atoms, or alternatively R<sup>2</sup> and R<sup>3</sup> bond together to form a ring and in that event, each is an alkylene group of 1 to 20 carbon atoms which optionally contains a hetero atom such as oxygen, sulfur or nitrogen, "a" is 0 or 1, and "b" is an integer of 1 to 4.

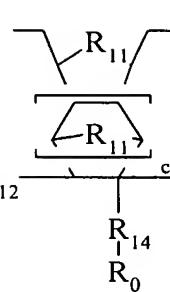
3. **(Previously presented)** The polymer of claim 1 having a partial structure of any one of the following formulae (2-1) to (2-5):



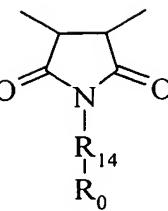
(2-1)



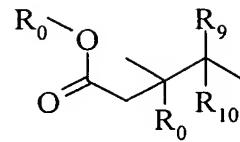
(2-2)



(2-3)



(2-4)



(2-5)

wherein R<sup>0</sup> is a group of formula (1) in claim 1,

R<sup>8</sup> to R<sup>10</sup> each are hydrogen, fluorine or a straight, branched or cyclic alkyl or fluorinated alkyl group of 1 to 20 carbon atoms,

R<sup>11</sup> is a methylene group, oxygen atom or sulfur atom,

R<sup>12</sup> and R<sup>13</sup> each are hydrogen, methyl or CH<sub>2</sub>CO<sub>2</sub>R<sup>15</sup>,

R<sup>14</sup> is a straight, branched or cyclic alkylene or fluorinated alkylene group of 1 to 20 carbon atoms,

R<sup>15</sup> is a straight, branched or cyclic alkyl or substituted alkyl group of 1 to 20 carbon atoms, and

“c” is 0 or 1.

4. **(Original)** A resist composition comprising the polymer of claim 1.

5. **(Previously presented)** A chemically amplified, positive resist composition comprising

(A) the polymer of claim 1,

(B) an organic solvent, and

(C) a photoacid generator.

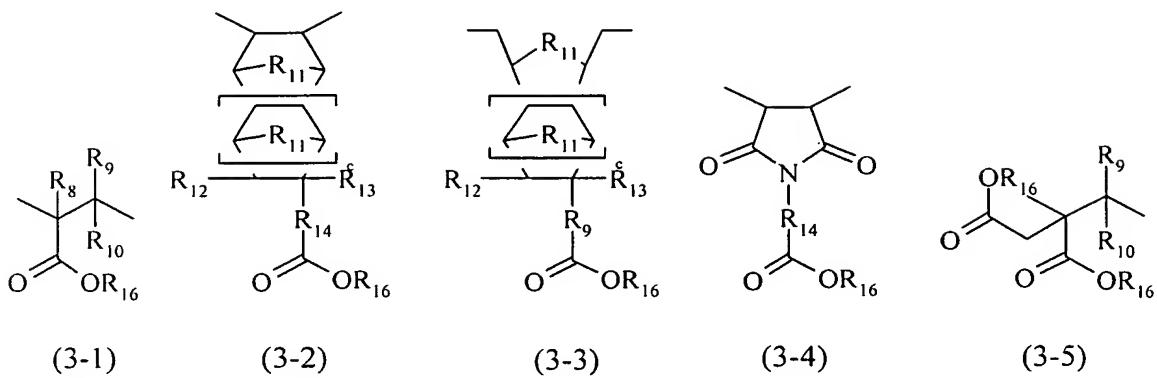
6. **(Original)** The resist composition of claim 5 further comprising (D) a basic compound.

7. **(Original)** The resist composition of claim 5 further comprising (E) a dissolution inhibitor.

8. **(Original)** A process for forming a resist pattern comprising the steps of:  
applying the resist composition of claim 4 onto a substrate to form a coating,  
heat treating the coating and then exposing it to high-energy radiation in a wavelength band of 100 to 180 nm or 1 to 30 nm through a photo mask, and  
optionally heat treating the exposed coating and developing it with a developer.

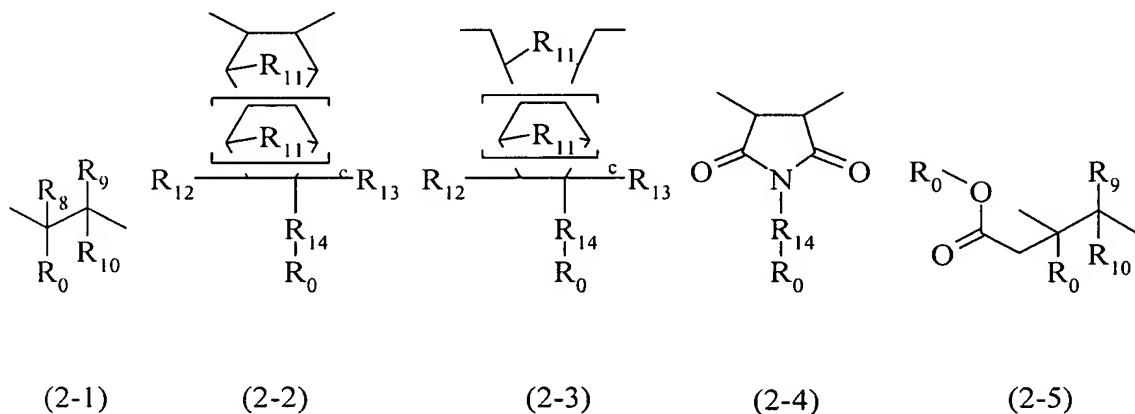
9. **(Original)** The pattern forming process of claim 8 wherein the high-energy radiation is an F<sub>2</sub> laser beam, Ar<sub>2</sub> laser beam or soft x-ray.

10. **(Previously presented)** The polymer of claim 3 which additionally comprises recurring units of one of formulae (3-1) to (3-5):



wherein, R<sup>8</sup> to R<sup>15</sup> and c are as defined above, and R<sup>16</sup> is an acid labile group.

11. (Previously presented) The polymer of claim 2 having a partial structure of any one of the following formulae (2-1) to (2-5):



wherein  $R^0$  is a group of formula (1a) in claim 2,

$\cdot R^8$  to  $R^{10}$  each are hydrogen, fluorine or a straight, branched or cyclic alkyl or fluorinated alkyl group of 1 to 20 carbon atoms,

$R^{11}$  is a methylene group, oxygen atom or sulfur atom,

$R^{12}$  and  $R^{13}$  each are hydrogen, methyl or  $CH_2CO_2R^{15}$ ,

$R^{14}$  is a straight, branched or cyclic alkylene or fluorinated alkylene group of 1 to 20 carbon atoms,

$R^{15}$  is a straight, branched or cyclic alkyl or substituted alkyl group of 1 to 20 carbon atoms, and

“c” is 0 or 1.

**12. (Previously presented)** A resist composition comprising the polymer of claim 2.

**13. (Previously presented)** A chemically amplified, positive resist composition comprising

- (A) the polymer of claim 2,
- (B) an organic solvent, and
- (C) a photoacid generator.

**14. (Previously presented)** The resist composition of claim 13 further comprising  
(D) a basic compound.

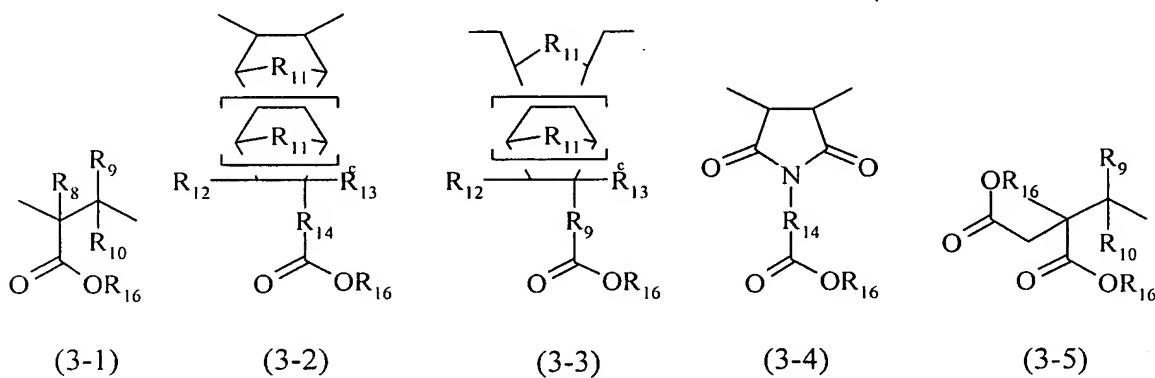
**15. (Previously presented)** The resist composition of claim 13 further comprising  
(E) a dissolution inhibitor.

**16. (Previously presented)** A process for forming a resist pattern comprising the steps of:

applying the resist composition of claim 12 onto a substrate to form a coating,  
heat treating the coating and then exposing it to high-energy radiation in a wavelength  
band of 100 to 180 nm or 1 to 30 nm through a photo mask, and  
optionally heat treating the exposed coating and developing it with a developer.

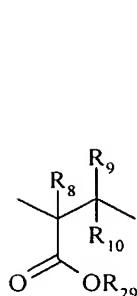
**17. (Previously presented)** The pattern forming process of claim 16 wherein the high-energy radiation is an  $F_2$  laser beam,  $Ar_2$  laser beam or soft x-ray.

**18. (Previously presented)** The polymer of claim 11 which additionally comprises one or more recurring units of one of formulae (3-1) to (3-5):

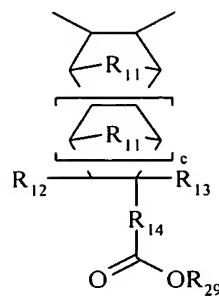


wherein, R<sup>8</sup> to R<sup>15</sup> and c are as defined above, and R<sup>16</sup> is an acid labile group.

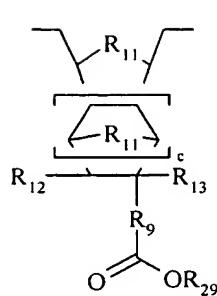
**19. (Previously presented)** The polymer of claim 3 which additional comprises one or more recurring units of one of the formulae (7-1) to (7-5)



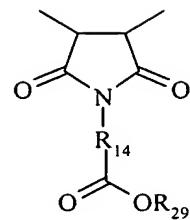
(7-1)



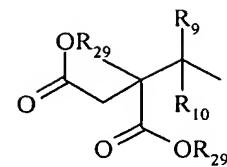
(7-2)



(7-3)



(7-4)

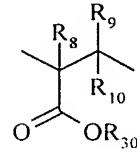


(7-5)

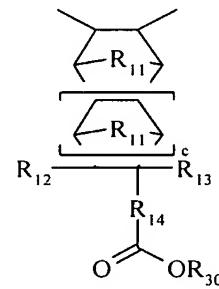
wherein,  $R^8$  to  $R^{15}$  and  $c$  are as defined above, and  $R^{29}$  is a fluorinated alkyl group having 2 to 20 carbon atoms.

**20. (Previously presented)**

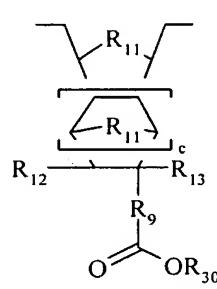
20. (Previously presented) The polymer of claim 3 which additional comprises one or more recurring units of one of the formulae (8-1) to (8-5):



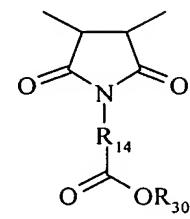
(8-1)



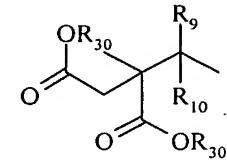
(8-2)



(8-3)



(8-4)

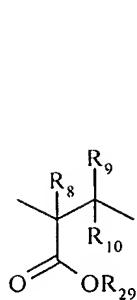


(8-5)

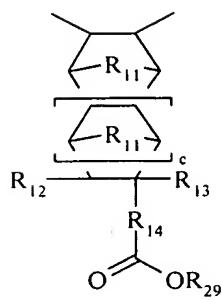
wherein, R<sup>8</sup> to R<sup>15</sup> and c are as defined above, and R<sup>30</sup> is hydrogen or an adhesive group.

**21. (Previously presented)**

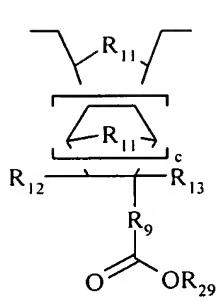
21. (Previously presented) The polymer of claim 11 which additional comprises one or more recurring units of one of the formulae (7-1) to (7-5)



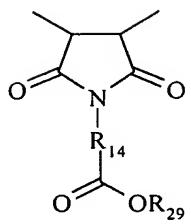
(7-1)



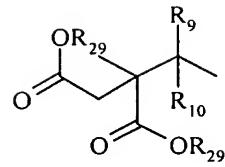
(7-2)



(7-3)



(7-4)



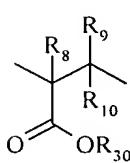
(7-5)

wherein,  $R^8$  to  $R^{15}$  and  $c$  are as defined above, and  $R^{29}$  is a fluorinated alkyl group having 2 to 20 carbon atoms.

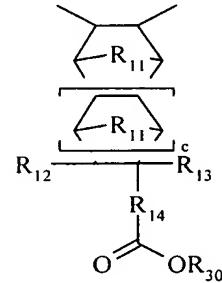
**22. (Previously presented)**

The polymer of claim 11 which additional comprises

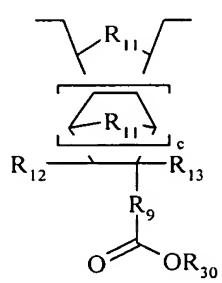
one or more recurring units of one of the formulae (8-1) to (8-5):



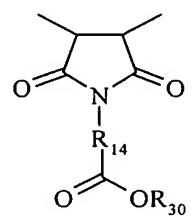
(8-1)



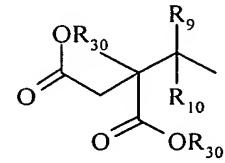
(8-2)



(8-3)



(8-4)



(8-5)

wherein,  $R^8$  to  $R^{15}$  and  $c$  are as defined above, and  $R^{30}$  is hydrogen or an adhesive group.